

**ANTIREFLECTION FILM, LAMINATED BODY INCLUDING ANTIREFLECTION FILM AND PRODUCTION OF ANTIREFLECTION FILM**

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**Abstract of JP2000171604**

**PROBLEM TO BE SOLVED:** To provide an antireflection film which has excellent antireflection effect and contamination resistance and which can be formed by the photosetting reaction even in the presence of oxygen by hardening a photosetting compsn. containing a specified compd. and a photoacid producing agent component with light. **SOLUTION:** This antireflection film is formed by hardening a photosetting compsn. containing at least one compd. selected from a group of hydrolytic silane compds. expressed by the formula of  $(R_1)PSi(X)_4-P$ , their hydrolyzed products and condensed products, and a photoacid producing agent component with light. In the formula, R<sub>1</sub> is a 1-12C nonhydrolyzable org. group, X is a hydrolyzable group, and p is an integer of 0 to 3. The antireflection film can be formed even in air without influenced by oxygen, and an excellent antireflection effect and contamination resistance of the obtd. antireflection film can be obtd.

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